

## Wafers

### 1. Silicon wafer

Parameter	UOM	2"	4"	4"
Crystal Orientation:	----	<100>	<100>	<100>
Type / Dopant:	----	P / Born	P / Born	P / Born
Crystal Method:	----	CZ	CZ	CZ
Slice Orientation:	degree	0°±0.5°	0°±0.5°	0°±0.5°
Diameter:	mm	50.8±0.3	100±0.3	100±0.3
Thickness:	µm	430±20	430±20	625±20
Resistivity:	Ohm-cm	<0.0015	<0.0015	<0.0015
Polish:	----	SSP	SSP	SSP
Primary Flat:	mm	16±1	32±2	32±2

### 2. GaAs wafer

Parameter	UOM	Customer's Requirements
Diameter	inch	2", 4", 6"
Growth Method:	----	VGF
Conduct Type:	----	S-C-N
Dopant:	----	GaAs-Si
Orientation:	----	(100)2°, 6°, 15° ± 0.5° off toward (011)
OF location/length:	----	EJ [ 0-1-1]± 0.5° /32.5±1
IF location/length:	----	EJ [ 0-1 1 ]± 0.5°/18±1
EPD:	----	Max: 5000
Thickness:	µm	350±25
Edge Rounding:	mmR	0.25
TTV/TIR:	µm	Max: 15
Surface Finish– front:	----	Polished
Surface Finish –back:	----	Etched
Partical Count:	----	<50 (size) > 0.3µm,Count/wafer)
Epi-Ready:	----	Yes